

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L17	166248	etch\$3 same silicon	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/03 07:49
L18	373	L17 same ((puls\$3 or modul\$3) same voltage)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/03 07:51
L19	225	L18 same (plasma same puls\$3 or modul\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/03 07:49
L20	108	L19 and @pd<"20010914"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/03 07:49
L21	60	L20 and (trench or recess or open\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/03 07:49
L22	2	L21 and ((polarity or ambipolar\$3) same plasma)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/03 07:49
L23	373	L17 same ((puls\$3 or modul\$3) same voltage)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/03 07:52
L24	40	23 and (substrate near electrode)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/02/03 07:52